Supporting Information

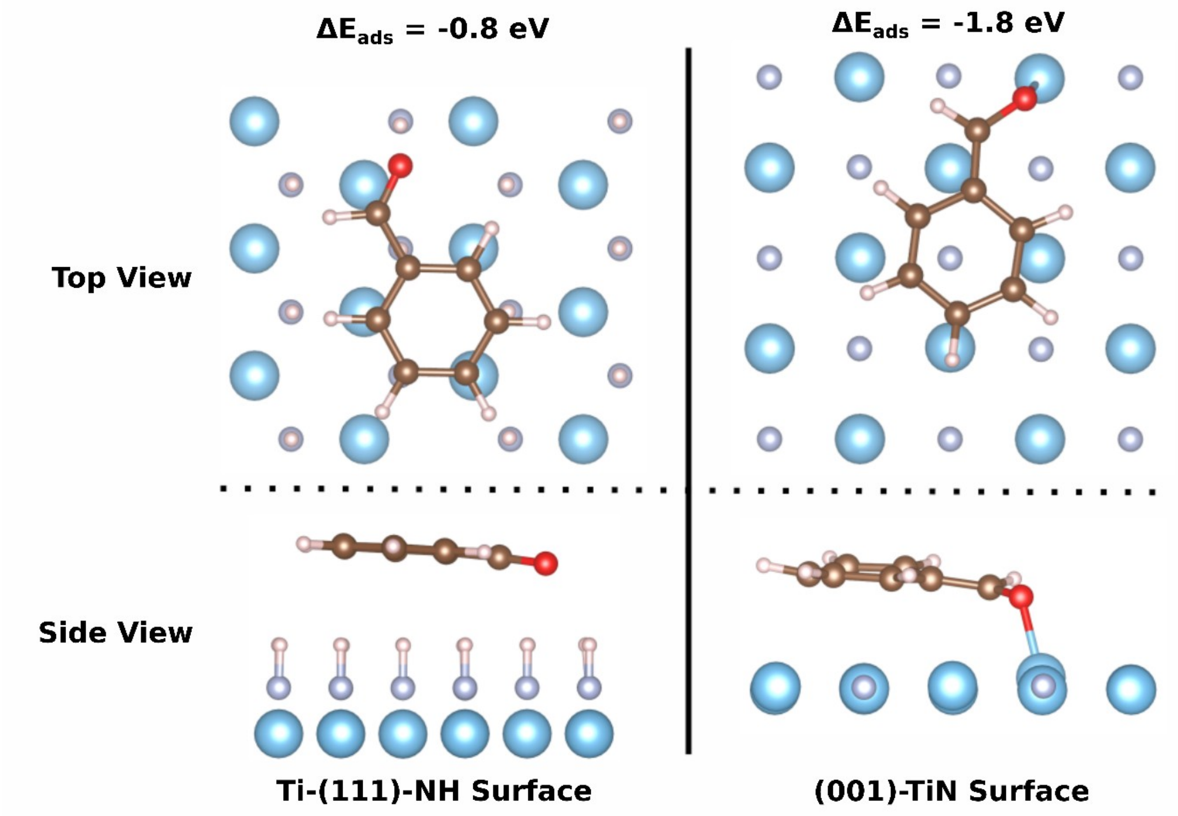

Figure 1:Top and Side view of Benzaldehyde adsorption on TiN surfaces (left) functionalized Ti-(111)-NH surface and (right) bare (001)-TiN surface. Headers correspond to adsorption energies on each surface.

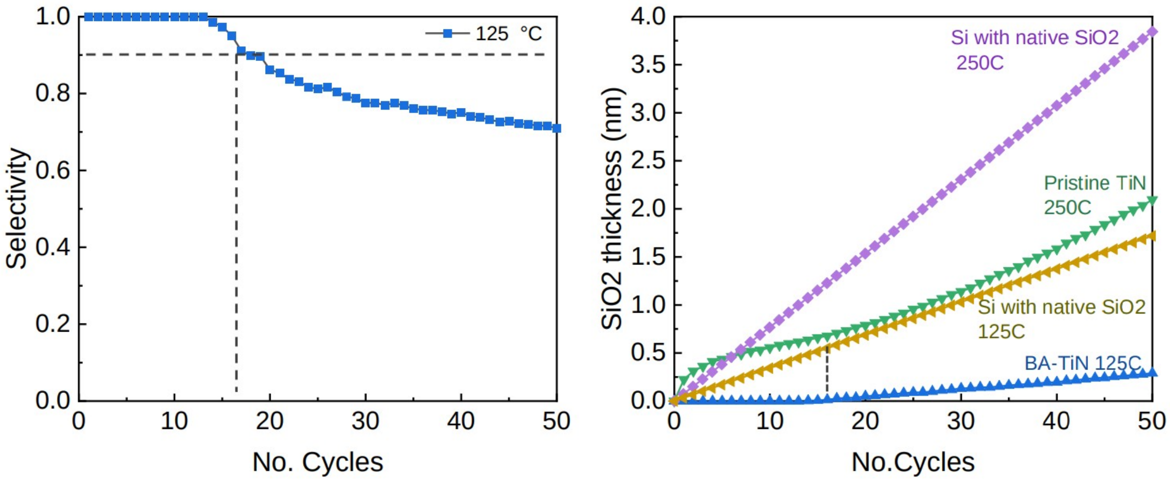

Figure 2: Thermal ALD selectivity of Benzaldehyde-inhibited TiN for SiO_2 deposition compared with Si (with native SiO_2) as growth area, at 125 °C. Selectivity >0.90 for 16 cycles.